

# Chemical Engineering 378

## *Science of Materials Engineering*

### Lecture 34 Electrical Properties



# Spiritual Thought

“If you have not chosen the Kingdom of God first, it will in the end make no difference what you have chosen instead.”

-William Law

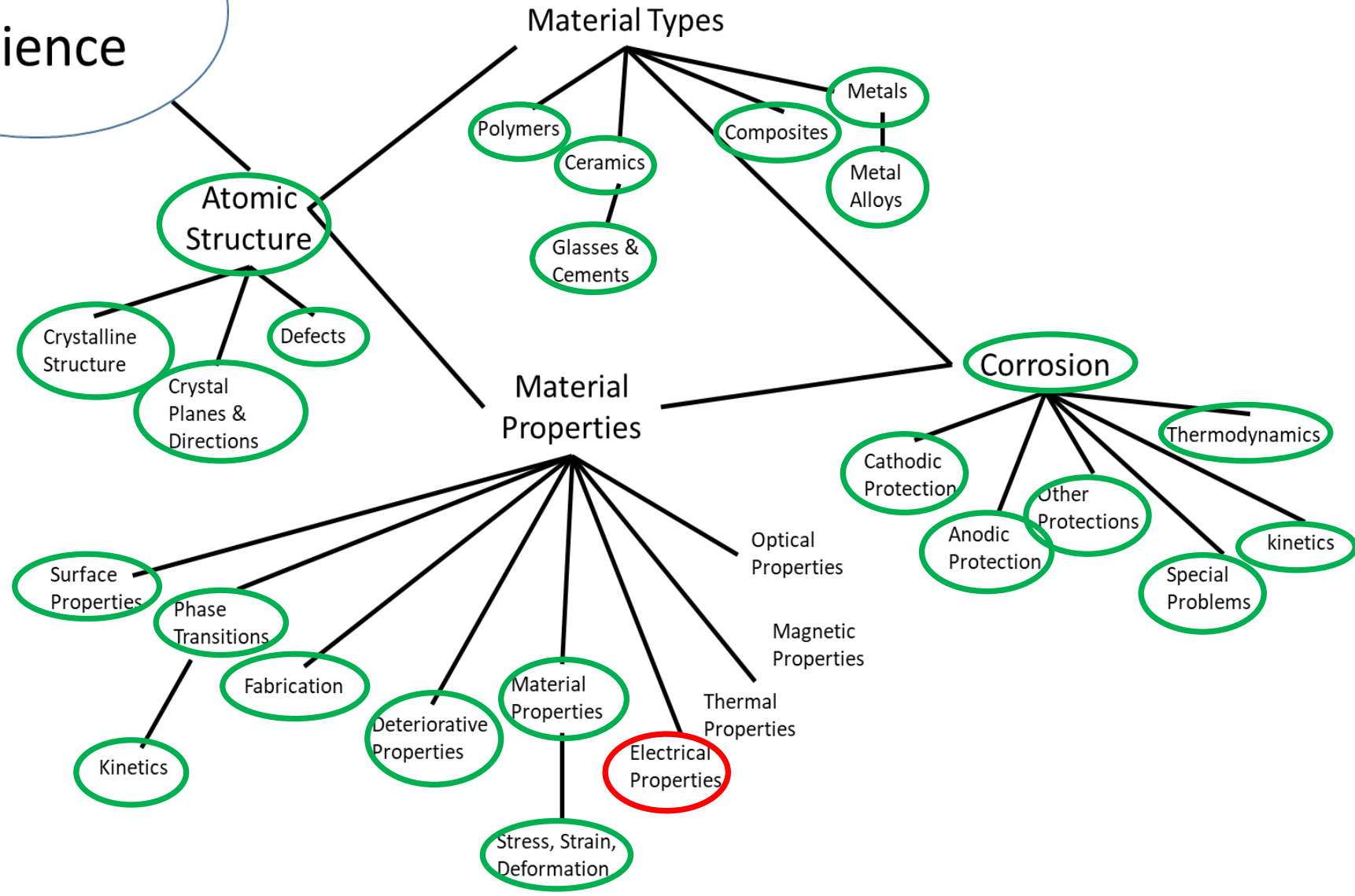
“This power that he had sought with such a singular focus, Midas realized, was not a blessing, but a curse. This ancient fable could not be more relevant for us in this day, when the media, academia and the Internet promote a “Midas mindset” that “discounts the importance of marriage” and suggests that fulfillment ‘is to be found in a rewarding career, in money, in freedom from the encumbrances of family life.’”

-W. Brad Wilcox



# Materials Roadmap

## Materials Science



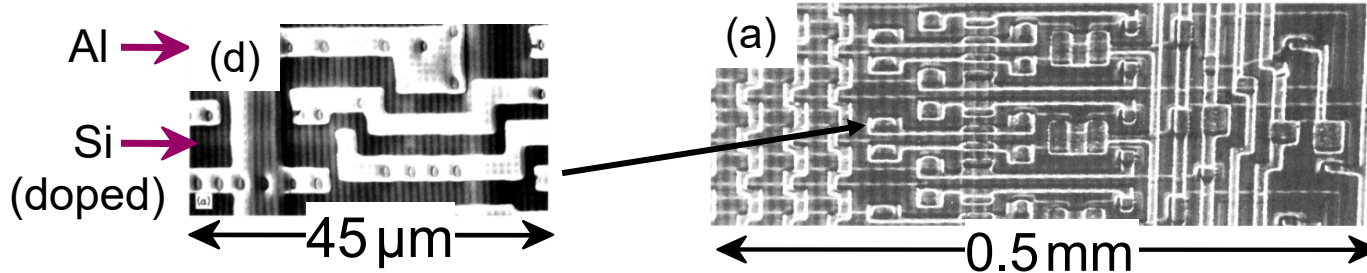
# Big Picture

- Electricity Equations/concepts
- Types of electrical materials
  - Conductors
  - Insulators
  - Semiconductors
- Semiconductor Behavior/Theory
- The “Why” behind each type (band gaps)
- Understand junction behaviors

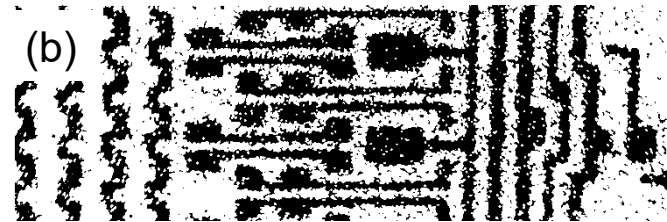


# View of an Integrated Circuit

- Scanning electron micrographs of an IC:



- A dot map showing location of Si (a semiconductor):
  - Si shows up as light regions.



- A dot map showing location of Al (a conductor):
  - Al shows up as light regions.

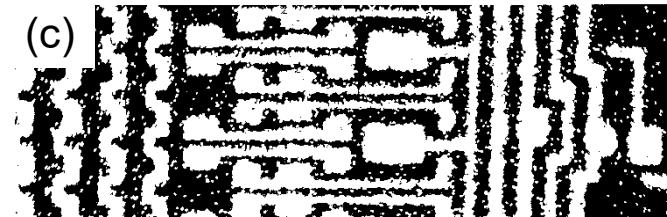


Fig. (d) from Fig. 12.27 (a), *Callister & Rethwisch 3e*.  
(Courtesy Nick Gonzales, National Semiconductor Corp., West Jordan, UT.)

Figs. (a), (b), (c) from Fig. 18.26, *Callister & Rethwisch 10e*.

# Electrical Conduction

- Ohm's Law:

$$V = IR$$

voltage drop (volts = J/C)  
C = Coulomb

current (amps = C/s)

resistance (Ohms)

- Resistivity,  $\rho$ :

-- a material property that is independent of sample size and geometry

$$\rho = \frac{RA}{\ell}$$

cross-sectional area of current flow

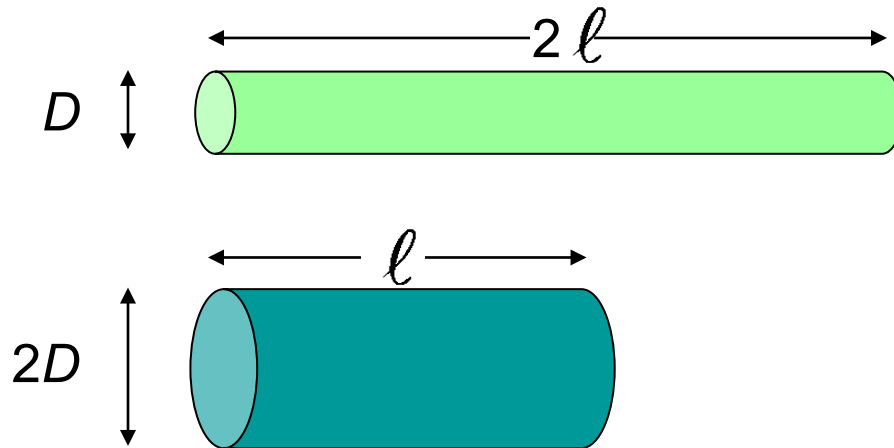
current flow path length

- Conductivity,  $\sigma$

$$\sigma = \frac{1}{\rho}$$

# Electrical Properties

- Which will have the greater resistance?



$$R_1 = \frac{2\rho\ell}{\pi\left(\frac{D}{2}\right)^2} = \frac{8\rho\ell}{\pi D^2}$$

$$R_2 = \frac{\rho\ell}{\pi\left(\frac{2D}{2}\right)^2} = \frac{\rho\ell}{\pi D^2} = \frac{R_1}{8}$$

- Analogous to flow of water in a pipe
- Resistance depends on sample geometry and size.

# Definitions

## Further definitions

$$\boxed{J = \sigma \mathcal{E}} \quad \Leftarrow \text{another way to state Ohm's law}$$

$$J \equiv \text{current density} \quad = \frac{\text{current}}{\text{surface area}} = \frac{I}{A} \quad \text{like a flux}$$

$$\mathcal{E} \equiv \text{electric field potential} = V/\ell$$

$$J = \sigma (V/\ell)$$

Electron flux      conductivity      voltage gradient



# Conductivity: Comparison

- Room temperature values  $(\text{Ohm-m})^{-1} = (\Omega - \text{m})^{-1}$

## METALS

### conductors

Silver	$6.8 \times 10^7$
Copper	$6.0 \times 10^7$
Iron	$1.0 \times 10^7$

## CERAMICS

Soda-lime glass	$10^{-10}$ - $10^{-11}$
Concrete	$10^{-9}$
Aluminum oxide	$<10^{-13}$

## SEMICONDUCTORS

Silicon	$4 \times 10^{-4}$
Germanium	$2 \times 10^0$
GaAs	$10^{-6}$

### semiconductors

## POLYMERS

Polystyrene	$<10^{-14}$
Polyethylene	$10^{-15}$ - $10^{-17}$

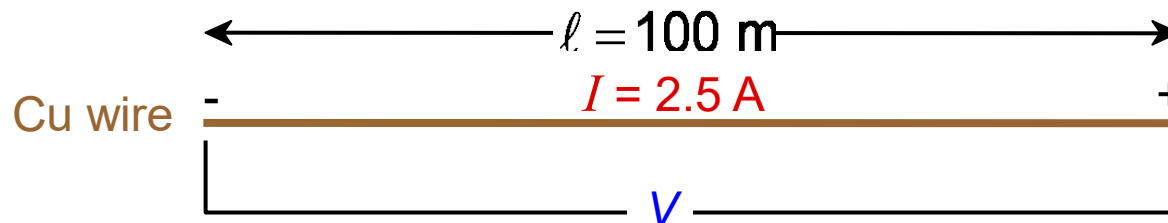
### insulators

Selected values from Tables 18.1, 18.3, and 18.4, *Callister & Rethwisch 10e*.



# Example: Conductivity Problem

What is the minimum diameter ( $D$ ) of the wire so that  $V < 1.5$  V?



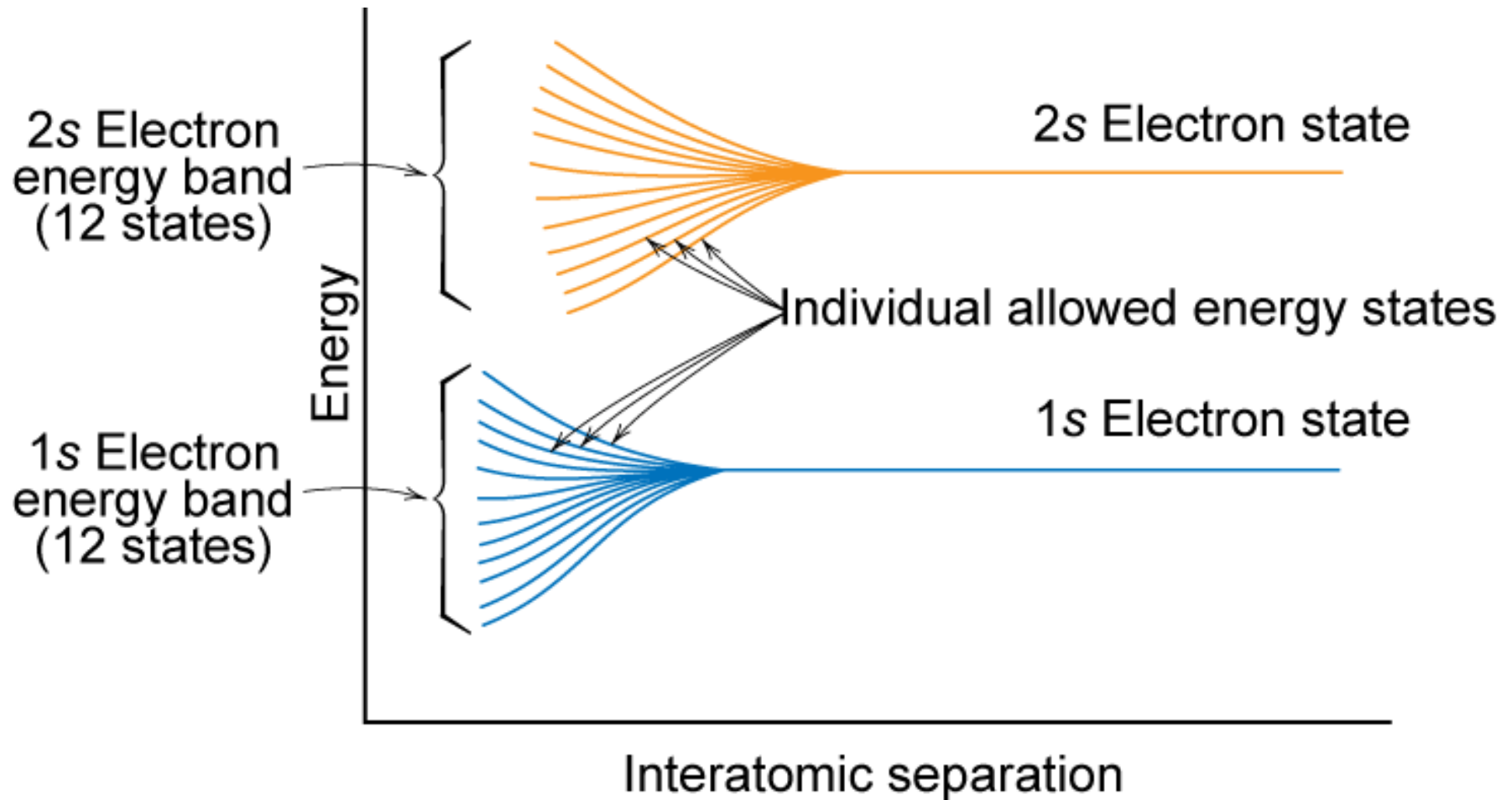
$$R = \frac{\ell}{A\sigma} = \frac{V}{I}$$

$\ell = 100$  m  
 $A = \frac{\pi D^2}{4}$   
 $\sigma = 6.07 \times 10^7 \text{ (Ohm-m)}^{-1}$   
 $V < 1.5$  V  
 $I = 2.5$  A

Solve to get  $D > 1.87$  mm



# Electron Energy Band Structures



Adapted from Fig. 18.2, *Callister & Rethwisch 10e*.

# Band Structure Representation

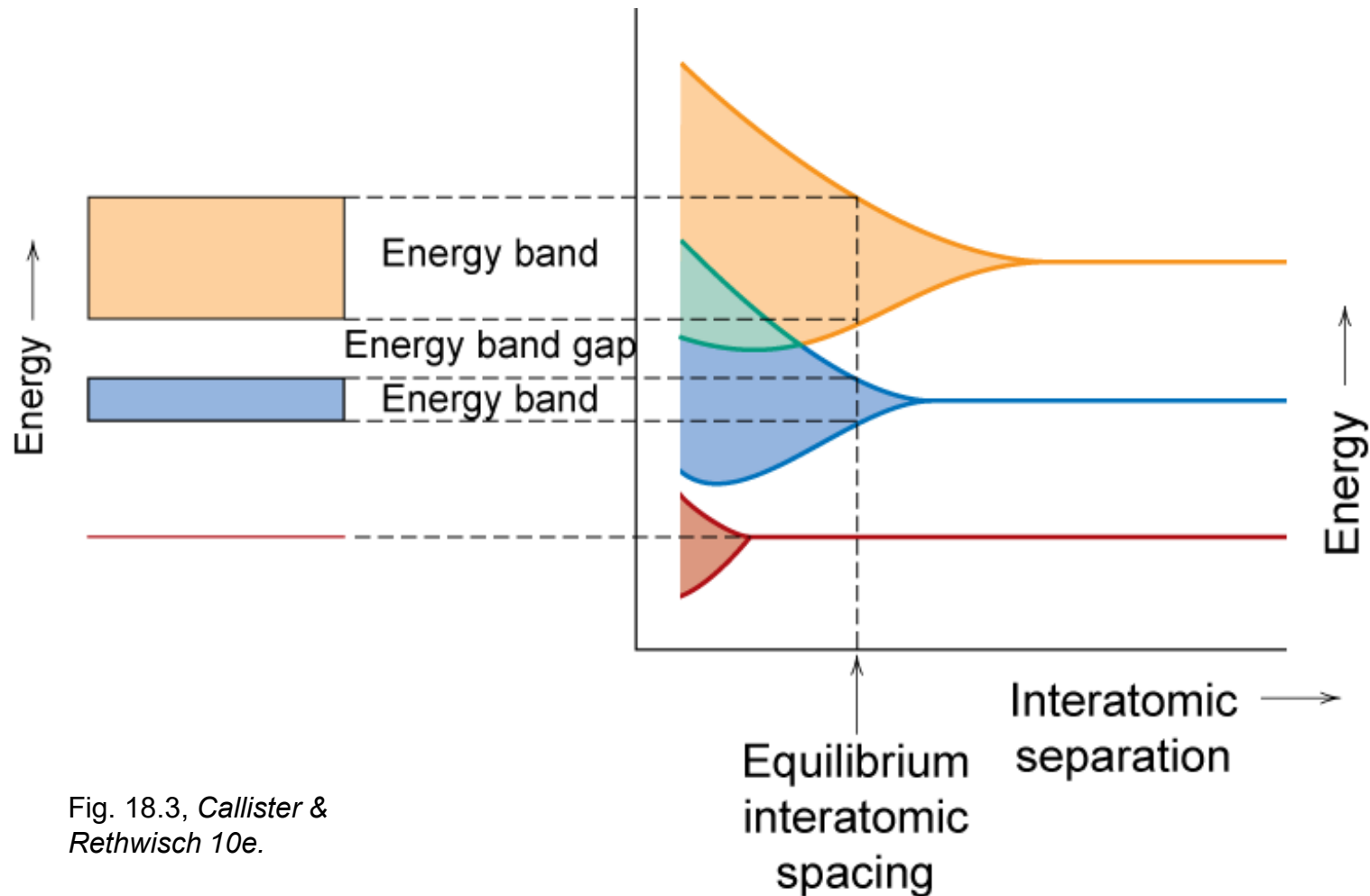
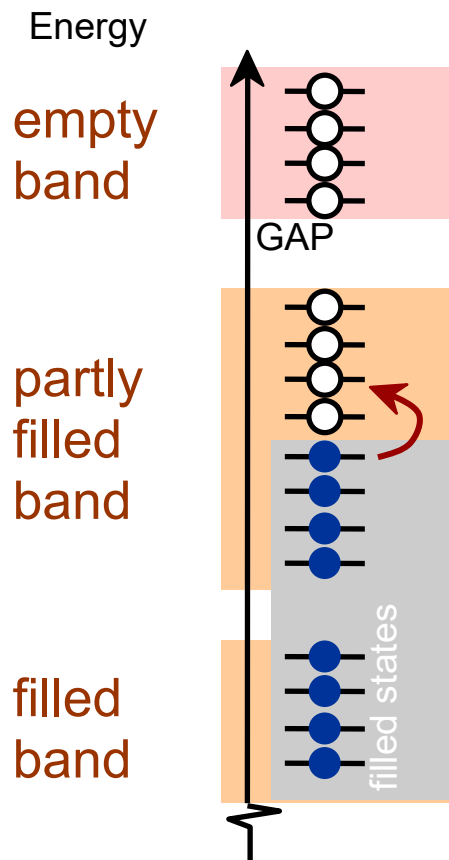


Fig. 18.3, Callister & Rethwisch 10e.

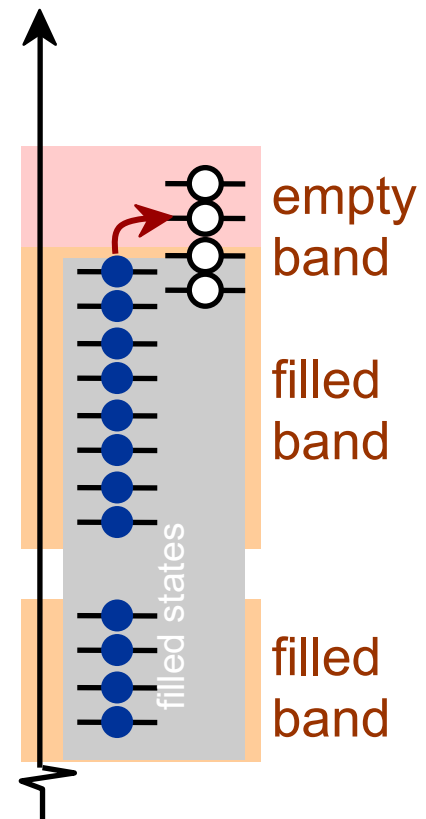
# Conduction & Electron Transport

- Metals (**Conductors**):
  - for metals empty energy states are adjacent to filled states.
  - thermal energy excites electrons into empty higher energy states.
  - two types of band structures for metals
    - partially filled band
    - empty band that overlaps filled band

Partially filled band

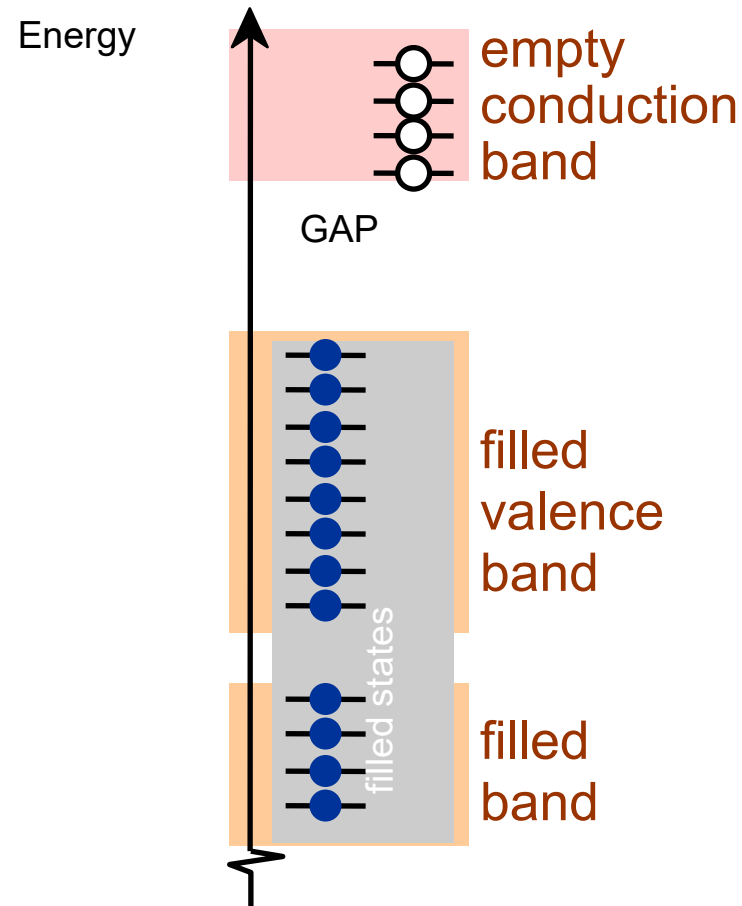


Overlapping bands



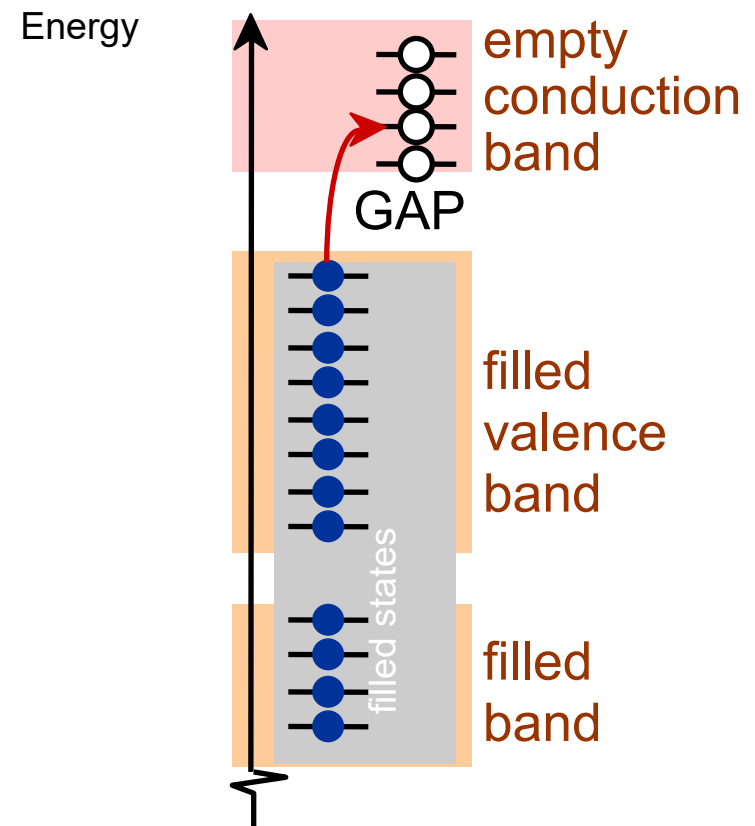
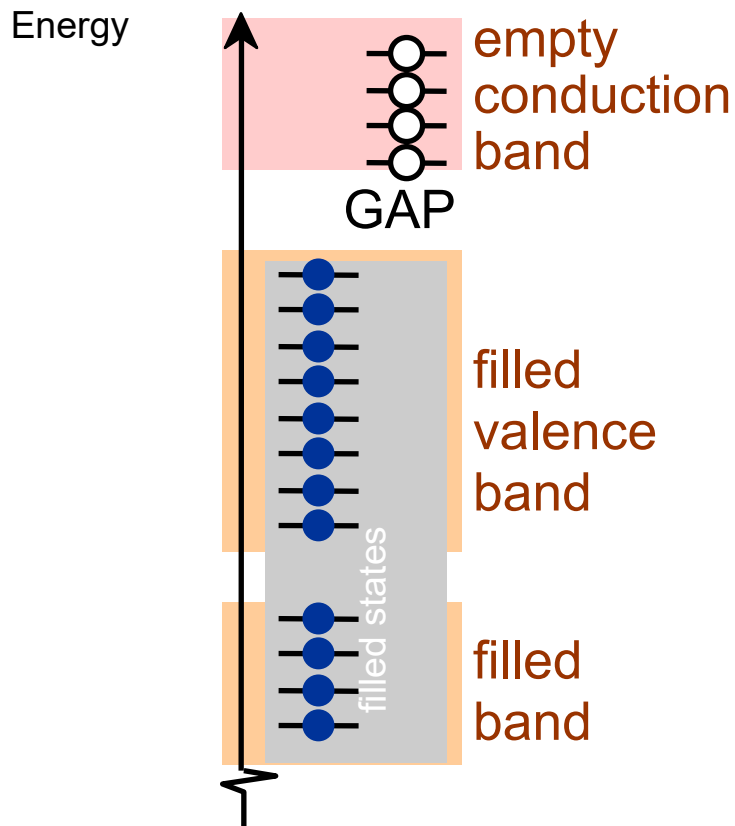
# Energy Band Structures: Insulators

- Wide band gap ( $> 2$  eV)
- Few electrons excited across band gap



# Energy Band Structures: Semiconductors

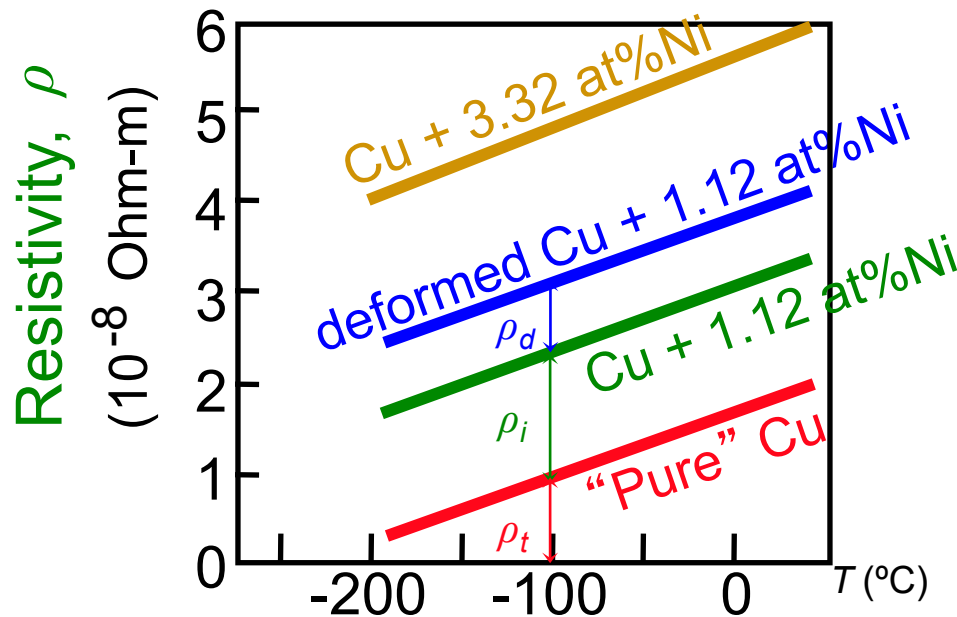
- Narrow band gap ( $< 2$  eV)
- Electrons with enough energy excited across band gap



# Metals: Influence of Temperature and Impurities on Resistivity

- Presence of imperfections increases resistivity
  - grain boundaries
  - dislocations
  - impurity atoms
  - vacancies

These act to scatter electrons so that they take a less direct path.



- Resistivity increases with:
  - temperature
  - wt% impurity
  - %CW

$$\rho = \rho_{\text{thermal}} + \rho_{\text{impurity}} + \rho_{\text{deformation}}$$

Fig. 18.8, Callister & Rethwisch 10e. (Based on data taken from J. O. Linde, *Ann. Physik*, 5, 1932, p. 219.)

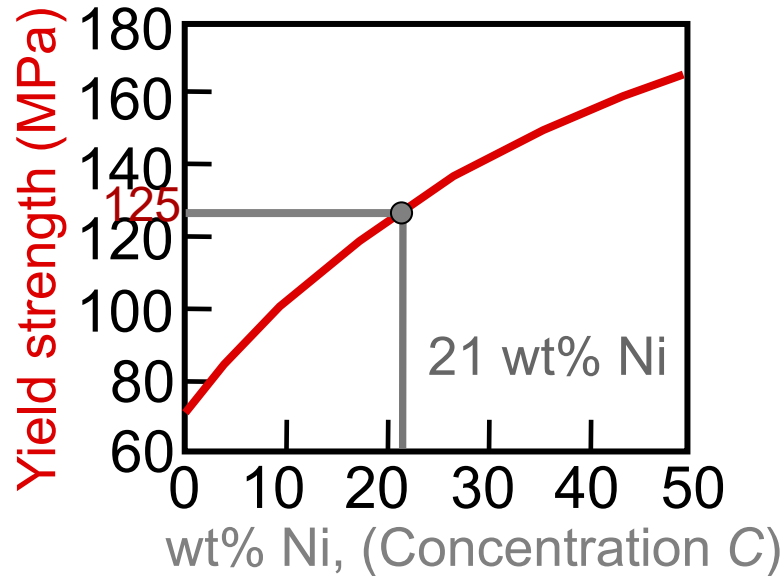


# Estimating Conductivity

- Question:

-- Estimate the electrical conductivity  $\sigma$  of a Cu-Ni alloy that has a yield strength of **125 MPa**.

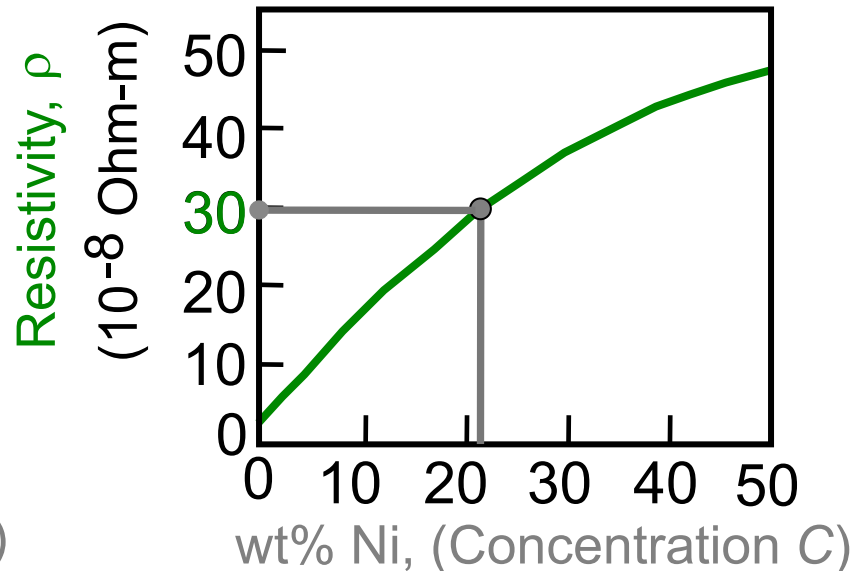
Adapted from Fig. 18.9, Callister & Rethwisch 10e.



Adapted from Fig. 7.16(b), Callister & Rethwisch 10e.

From step 1:

$$C_{\text{Ni}} = 21 \text{ wt\% Ni}$$

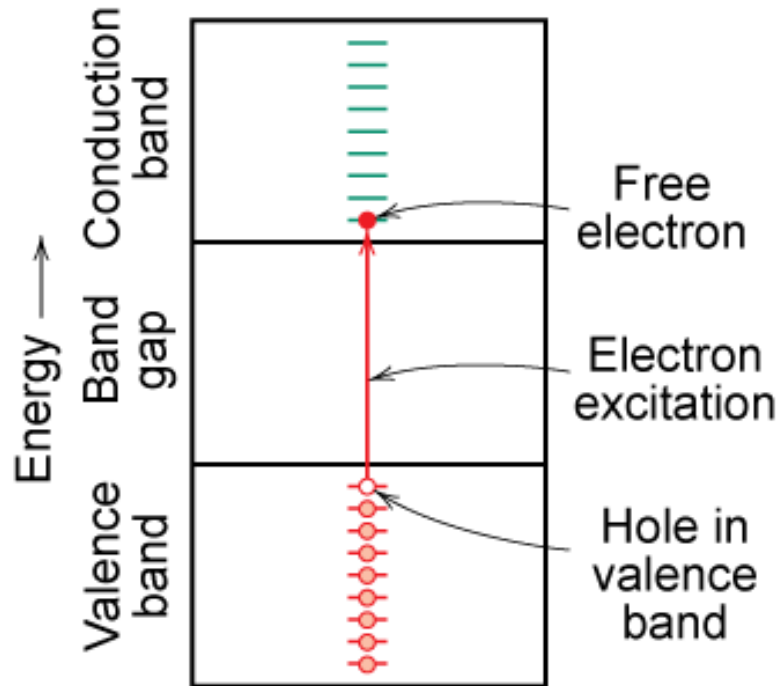


$$\rho = 30 \times 10^{-8} \text{ Ohm-m}$$

$$\sigma = \frac{1}{\rho} = 3.3 \times 10^6 (\text{Ohm-m})^{-1}$$

# Charge Carriers in Insulators and Semiconductors

Fig. 18.6 (b), Callister & Rethwisch 10e.



Two types of electronic charge carriers:

## Free Electron

- negative charge
- in conduction band

## Hole

- positive charge
- vacant electron state in the valence band

Move at different speeds - **drift velocities**

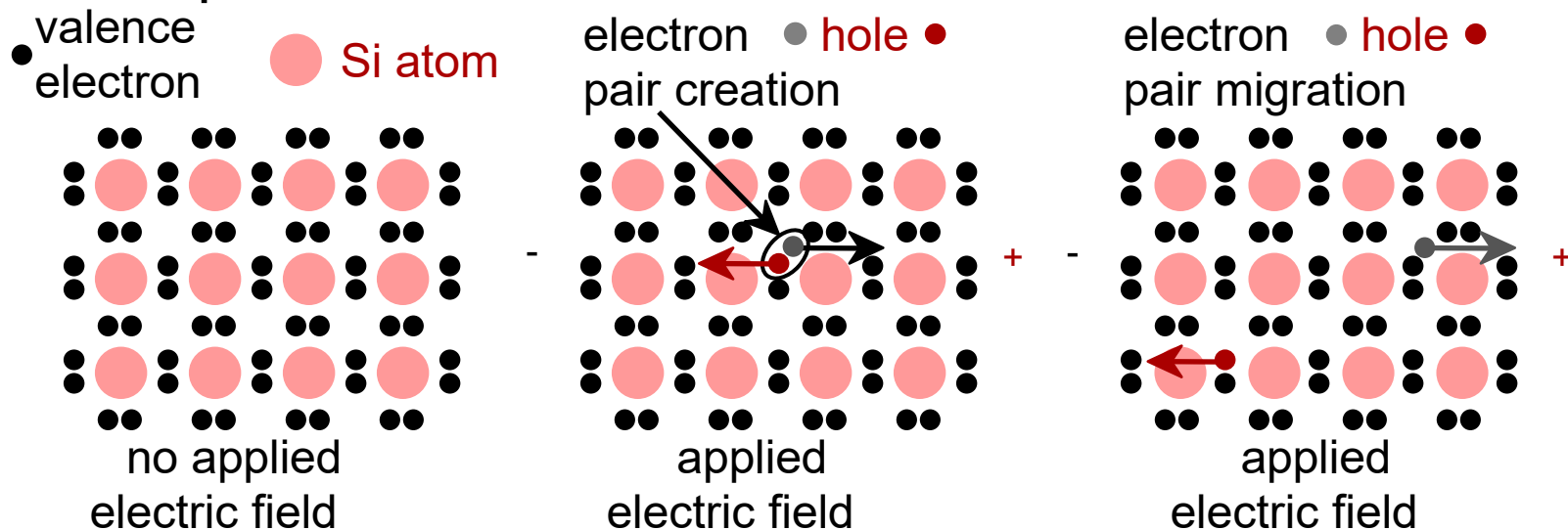
# Intrinsic Semiconductors

- Pure material semiconductors: e.g., silicon & germanium
  - Group IVA materials
- Compound semiconductors
  - III-V compounds
    - Ex: GaAs & InSb
  - II-VI compounds
    - Ex: CdS & ZnTe
  - The wider the electronegativity difference between the elements the wider the energy gap.



# Intrinsic Semiconduction in Terms of Electron and Hole Migration

- Concept of electrons and holes:



- Electrical Conductivity given by:

Adapted from Fig. 18.10,  
Callister & Rethwisch 10e.

$$\sigma = n |e| \mu_e + p |e| \mu_h$$

# electrons/m<sup>3</sup>      electron mobility      # holes/m<sup>3</sup>      hole mobility

# Number of Charge Carriers

## Intrinsic Conductivity

$$\sigma = n|e|\mu_e + p|e|\mu_h$$

- for intrinsic semiconductor  $n = p = n_i$

$$\therefore \sigma = n_i|e|(\mu_e + \mu_h)$$

- Ex: GaAs

$$n_i = \frac{\sigma}{|e|(\mu_e + \mu_h)} = \frac{10^{-6}(\Omega \cdot \text{m})^{-1}}{(1.6 \times 10^{-19} \text{ C})(0.85 + 0.45 \text{ m}^2/\text{V} \cdot \text{s})}$$

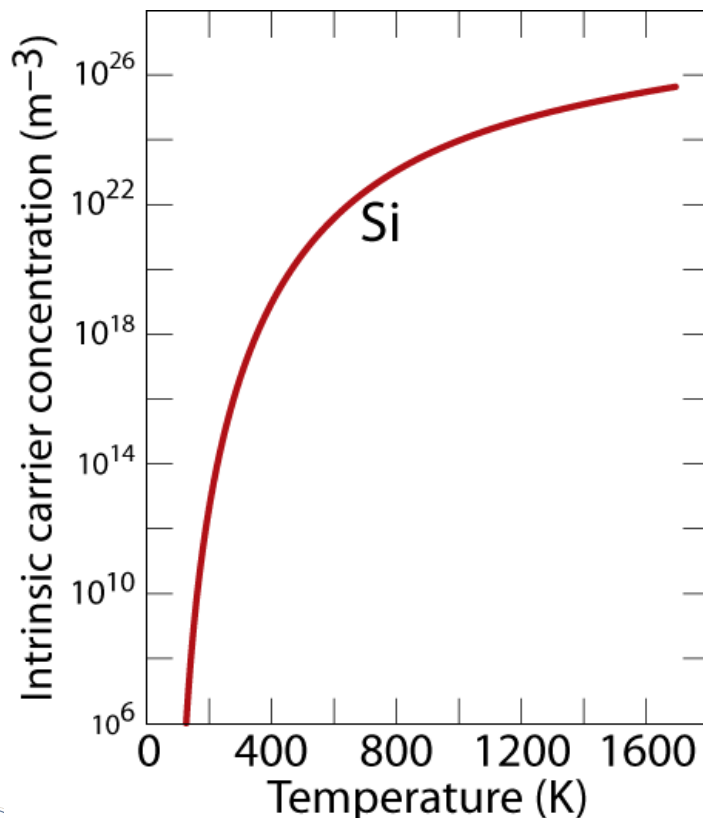
For GaAs  $n_i = 4.8 \times 10^{24} \text{ m}^{-3}$

For Si  $n_i = 1.3 \times 10^{16} \text{ m}^{-3}$



# Intrinsic Semiconductors: Conductivity vs $T$

- Data for **Pure Silicon**:
  - $\sigma$  increases with  $T$
  - opposite to metals



$$\sigma = n_i |e| (\mu_e + \mu_h)$$

$$n_i \propto e^{-E_{\text{gap}}/kT}$$

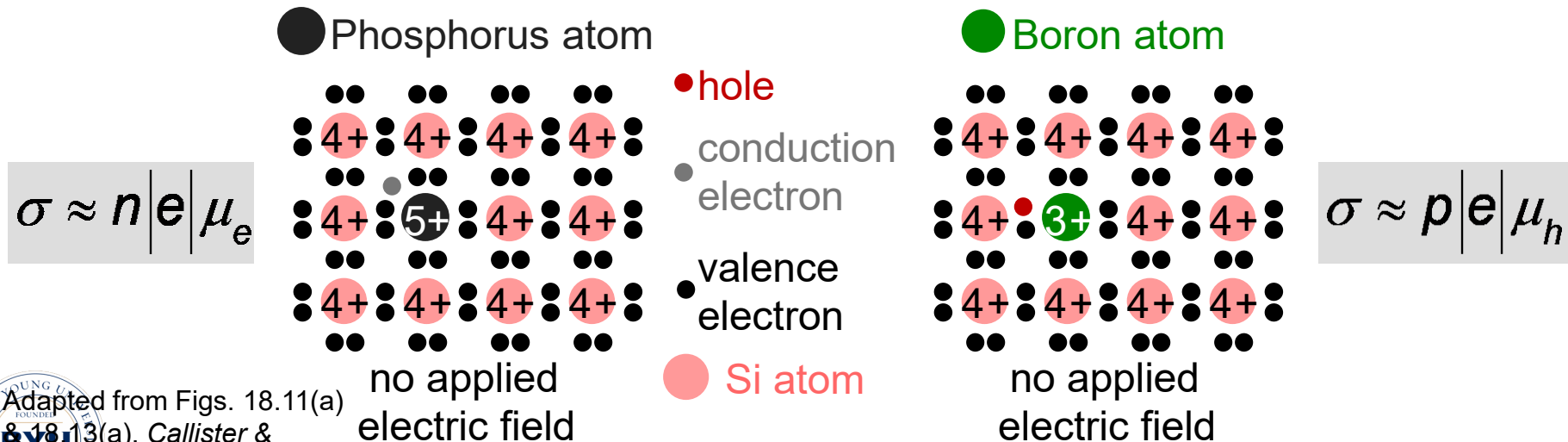
material	band gap (eV)
Si	1.11
Ge	0.67
GaP	2.25
CdS	2.40

Selected values from Table 18.3,  
*Callister & Rethwisch 10e.*

Adapted from Fig. 18.15,  
*Callister & Rethwisch 10e.*

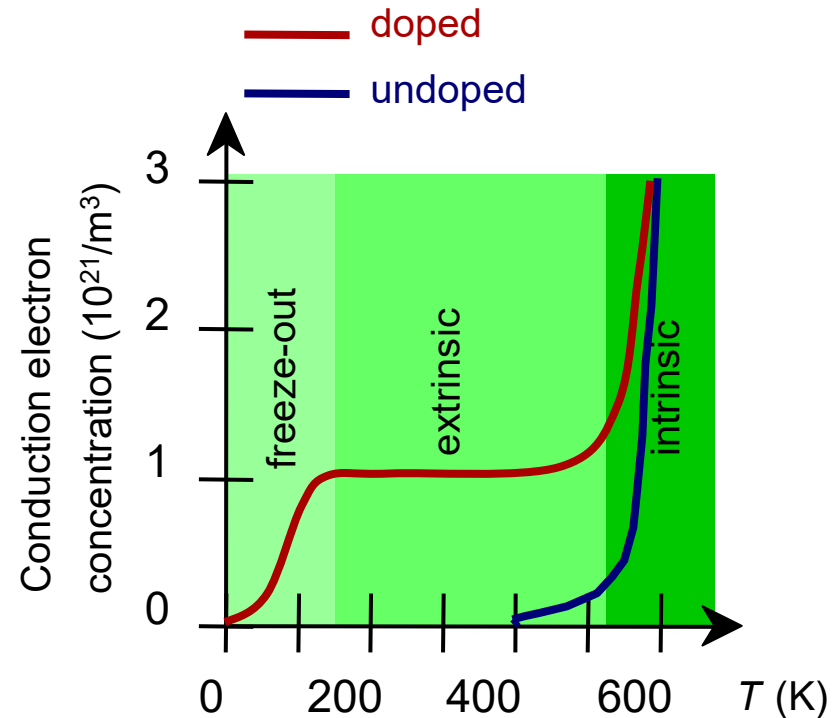
# Intrinsic vs Extrinsic Conduction

- **Intrinsic:**
  - case for pure Si
  - # electrons = # holes ( $n = p$ )
- **Extrinsic:**
  - electrical behavior is determined by presence of impurities that introduce excess electrons or holes
  - $n \neq p$
- **$n$ -type Extrinsic:** ( $n \gg p$ )
- **$p$ -type Extrinsic:** ( $p \gg n$ )



# Extrinsic Semiconductors: Conductivity vs. Temperature

- Data for Doped Silicon:
  - $\sigma$  increases with doping
  - reason: imperfection sites lower the activation energy to produce mobile electrons.
- Comparison: **intrinsic** vs extrinsic conduction...
  - extrinsic doping level:  $10^{21}/\text{m}^3$  of a *n*-type donor impurity (such as P).
  - for  $T < 100$  K: "freeze-out", thermal energy insufficient to excite electrons.
  - for  $150 \text{ K} < T < 450 \text{ K}$ : "extrinsic"
  - for  $T \gg 450 \text{ K}$ : "intrinsic"



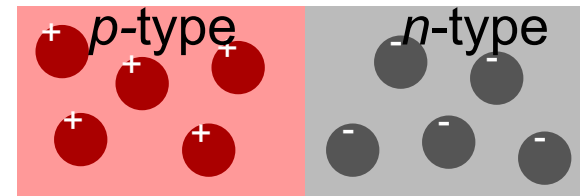
Adapted from Fig. 18.16, *Callister & Rethwisch 10e*.  
 (From S. M. Sze, *Semiconductor Devices, Physics and Technology*. Copyright © 1985 by Bell Telephone Laboratories, Inc. Reprinted by permission of John Wiley & Sons, Inc.)



# $p$ - $n$ Rectifying Junction

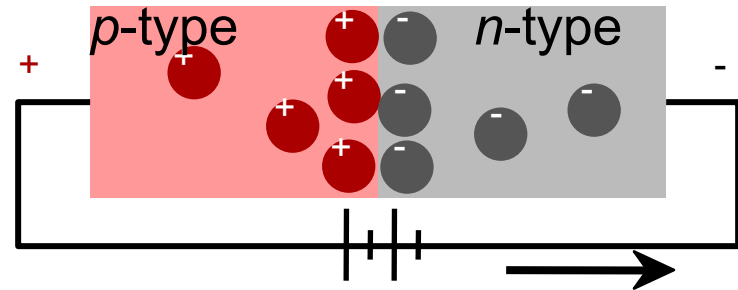
- Allows flow of electrons in one direction only (e.g., useful to convert alternating current to direct current).
- Processing: diffuse P into one side of a B-doped crystal.

-- No applied potential:  
no net current flow.

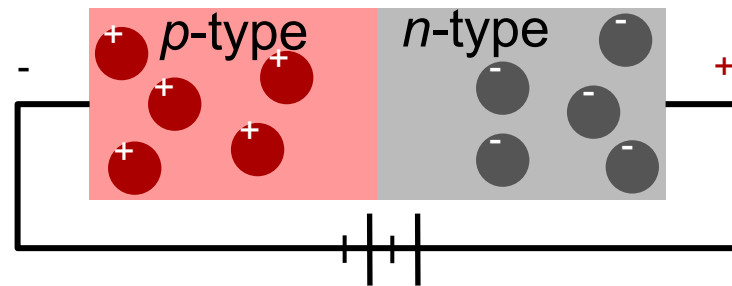


Adapted from  
Fig. 18.20,  
Callister &  
Rethwisch  
10e.

-- Forward bias: carriers  
flow through  $p$ -type and  
 $n$ -type regions; holes and  
electrons recombine at  
 $p$ - $n$  junction; current flows.



-- Reverse bias: carriers  
flow away from  $p$ - $n$  junction;  
junction region depleted of  
carriers; little current flow.



# Properties of Rectifying Junction

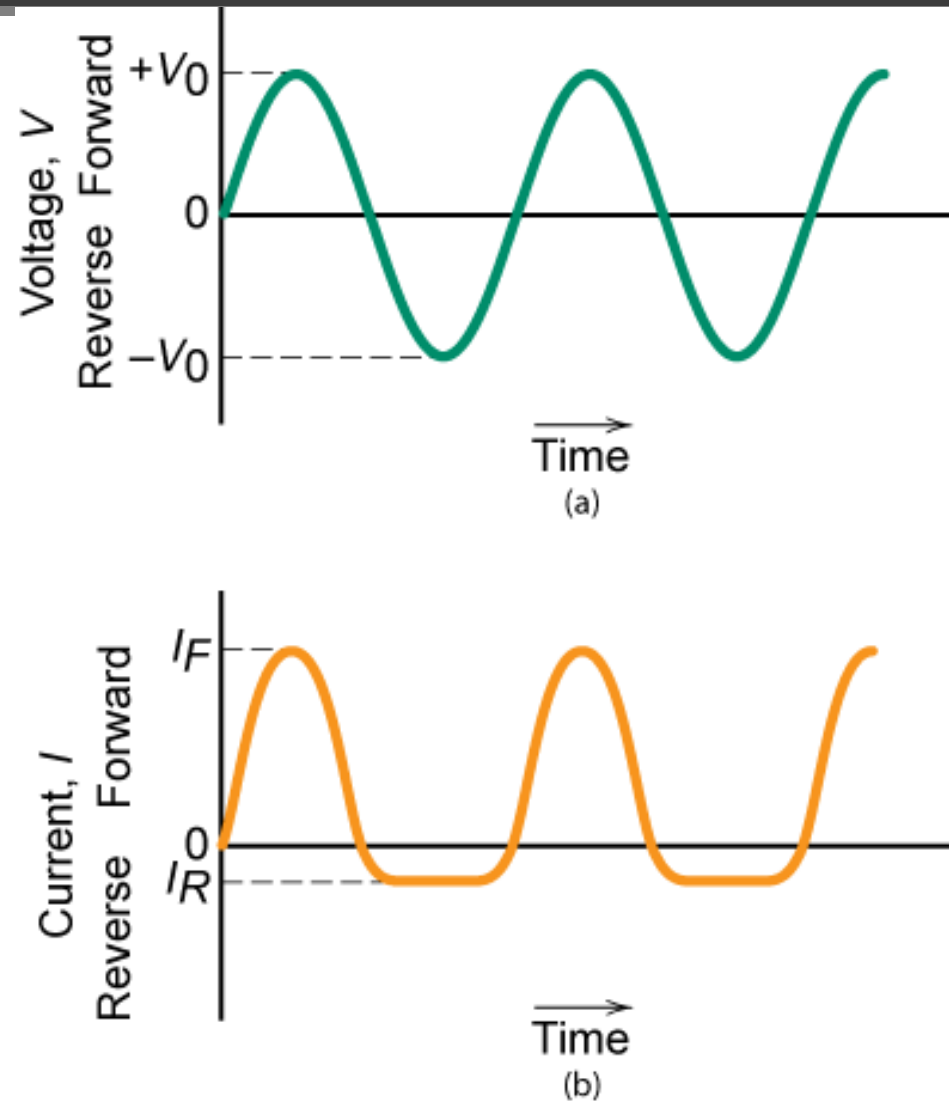
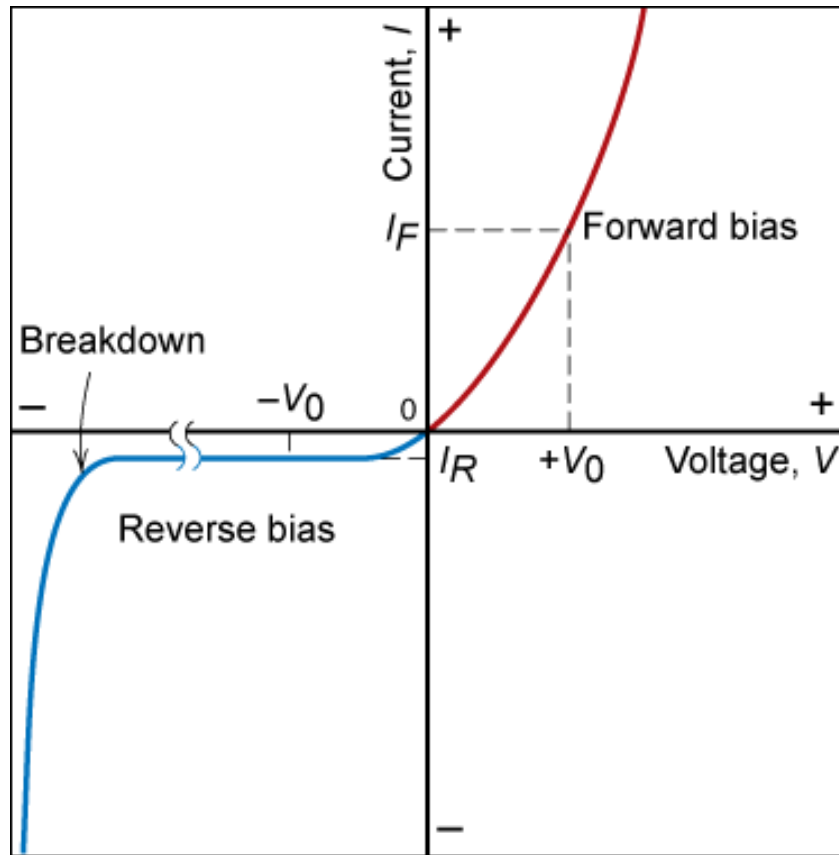


Fig. 18.21, Callister & Rethwisch 10e.

Fig. 18.22, Callister & Rethwisch 10e.

# Junction Transistor

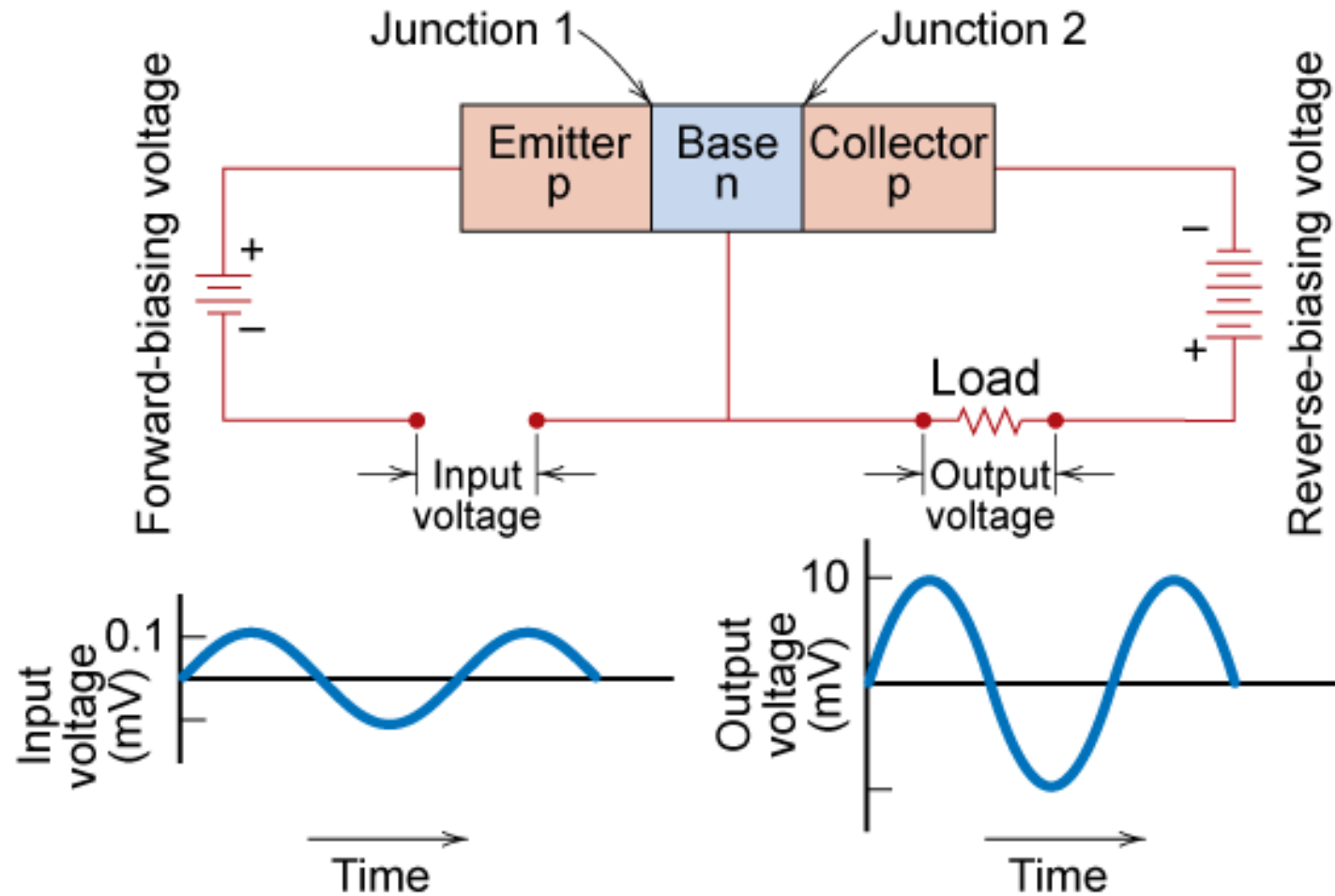


Fig. 18.23, Callister & Rethwisch 10e.

# MOSFET Transistor

## Integrated Circuit Device

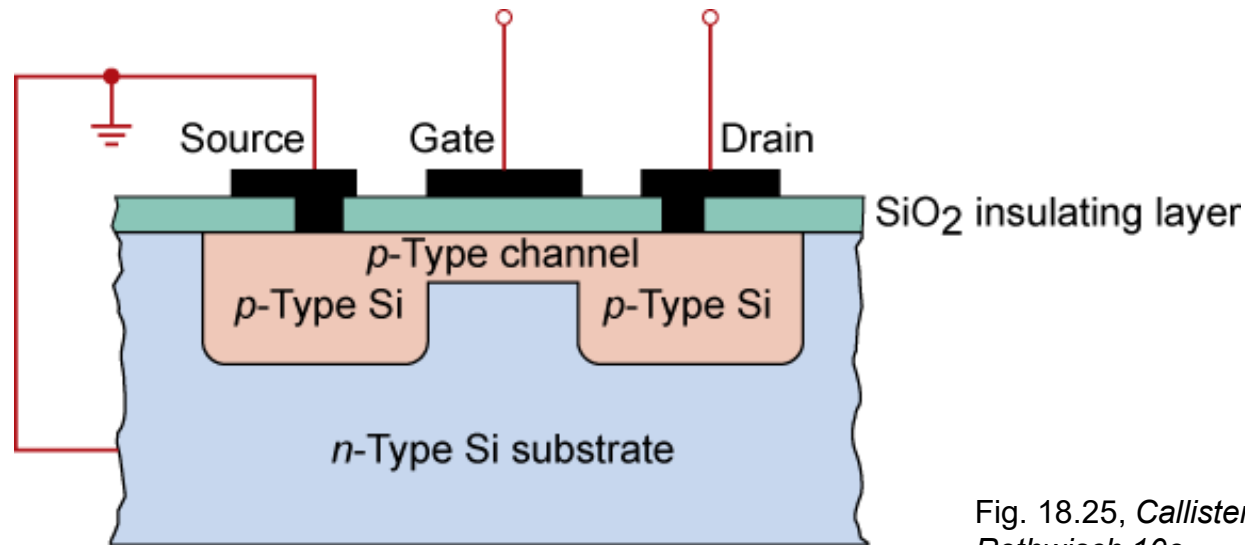
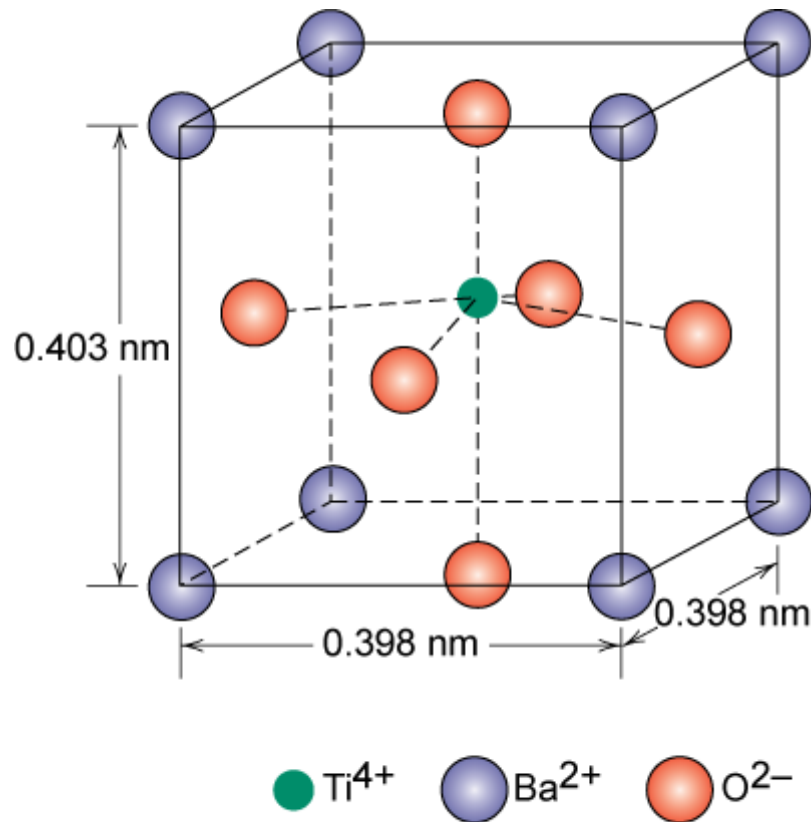


Fig. 18.25, Callister & Rethwisch 10e.

- MOSFET (metal oxide semiconductor field effect transistor)
- Integrated circuits - state of the art ca. 50 nm line width
  - ~ 1,000,000,000 components on chip
  - chips formed one layer at a time

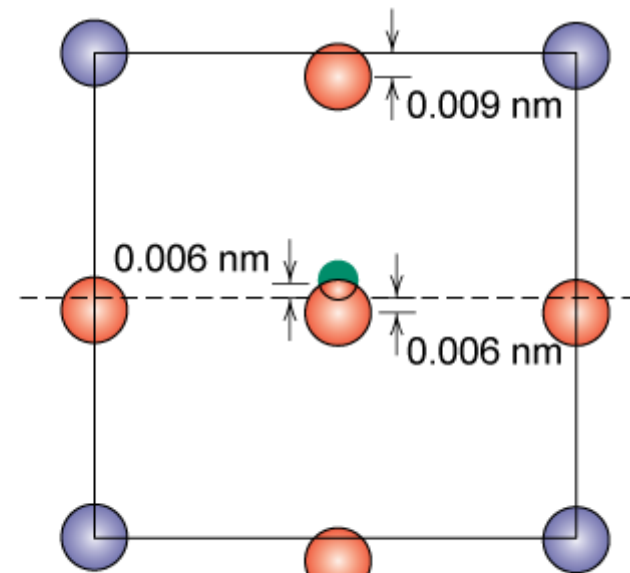
# Ferroelectric Ceramics

- Experience spontaneous polarization



(a)

$\text{BaTiO}_3$  -- ferroelectric below its Curie temperature ( $120^\circ \text{C}$ )



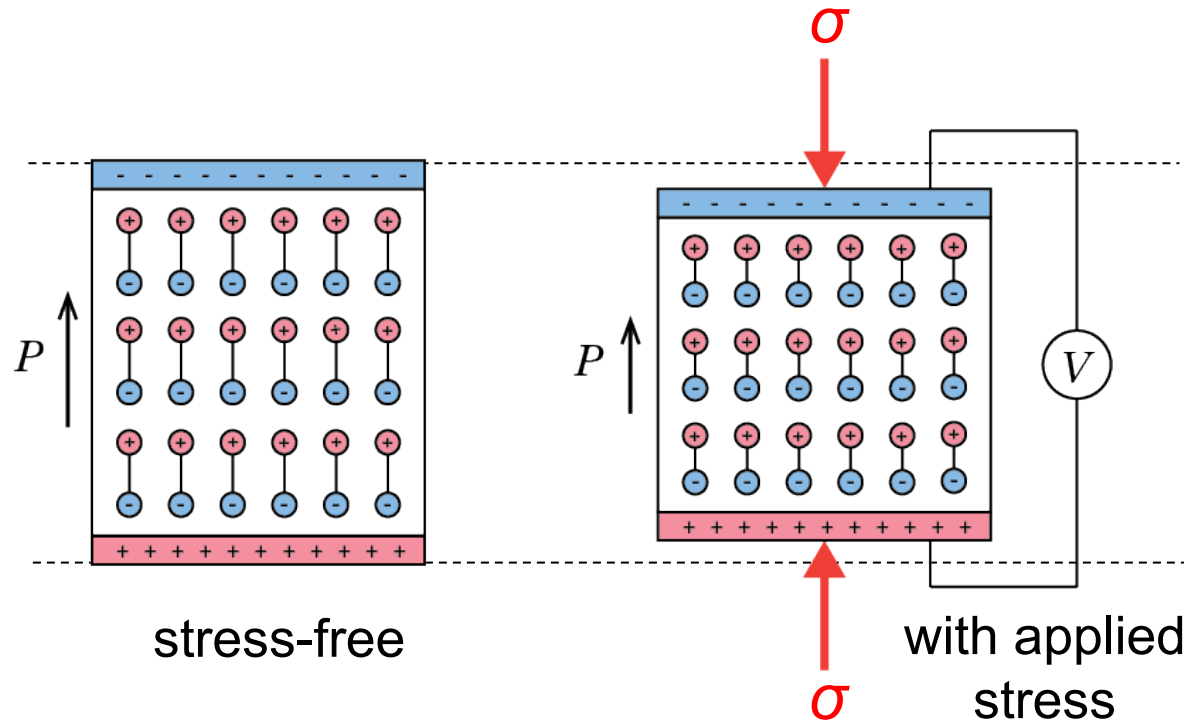
(b)

Fig. 18.34, Callister & Rethwisch 10e.

# Piezoelectric Materials

## Piezoelectricity

- application of stress induces voltage
- application of voltage induces dimensional change



Adapted from Fig. 18.35, *Callister & Rethwisch 10e*.  
 (From L. H. Van Vlack, *A Textbook of Materials Technology*,  
 Addison-Wesley, 1973. Reproduced with permission of the  
 estate of Lawrence H. Van Vlack.)